

## **AMENDMENTS TO THE CLAIMS**

### **Claims 1-12 (Canceled)**

**Claim 13 (New)** A substrate cleaning apparatus for cleaning a substrate by supplying a cleaning liquid and then drying a cleaned substrate, comprising:

a substrate holding mechanism configured to hold the substrate; and

a rotating mechanism configured to rotate said substrate holding mechanism;

wherein said substrate holding mechanism has at least three arms having an inclined surface, and said inclined surface of each of said at least three arms is inclined downwardly toward radially outward direction and comprises a liquid repellent material or a coating of a liquid repellent material; and

wherein said rotating mechanism has a first member comprising a cup-like member, and said cup-like member comprises a liquid repellent material or a coating of a liquid repellent material.

**Claim 14 (New)** A substrate cleaning apparatus according to claim 13, wherein said rotating mechanism has said first member and a second member, and said first member is located above said second member and an outer periphery of said first member is located radially outwardly of an inner periphery of said second member.

**Claim 15 (New)** A substrate cleaning apparatus according to claim 13, wherein said substrate holding mechanism holds an outer peripheral portion of the substrate.

**Claim 16 (New)** A substrate cleaning apparatus according to claim 13, wherein said rotating mechanism rotates said substrate holding mechanism at a variable rotational speed.

**Claim 17 (New)** A substrate cleaning method for cleaning a substrate by supplying a cleaning liquid and then drying a cleaned substrate, comprising:

holding the substrate by a substrate holding mechanism; and

rotating the substrate held by said substrate holding mechanism by a rotating mechanism to remove droplets from the substrate and dry the substrate;

wherein said substrate holding mechanism has at least three arms having an inclined surface, and said inclined surface of each of said at least three arms is inclined downwardly toward radially outward direction and comprises a liquid repellent material or a coating of a liquid repellent material;

wherein said rotating mechanism has a cup-like member, and said cup-like member comprises a liquid repellent material or a coating of a liquid repellent material; and

wherein a rotational speed of the substrate is changed stepwise by said rotating mechanism.

**Claim 18 (New)** A substrate cleaning method according to claim 17, wherein said rotational speed of the substrate comprises a low rotational speed of the substrate for removing droplets from components of said substrate holding mechanism and a high rotational speed of the substrate for spin-drying the substrate.